

103.0
2/6
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

(Case No. 98,162-B)

In re Application of:

)

DeGendt, et al.

)

Serial No.: 09/207,546

)

Filed: December 8, 1998

)

For: METHOD FOR REMOVING ORGANIC
CONTAMINANTS FROM A
A SEMICONDUCTOR SURFACE

)
)
)

Group Art Unit: 1746

Examiner: Ahmed

Commissioner for Patents
Washington, D.C. 20231



AMENDMENT

Dear Sir:

In response to the outstanding Office Action mailed August 30, 2000, please enter the following remarks and amendments in the above-referenced patent application.

IN THE CLAIMS

Please cancel claims 1-26, 34 and 36-39 without prejudice. Please amend claim 29 as follows:

A1
29. (Amended) A method for removing contaminants from a silicon substrate comprising the steps:
holding said substrate in a tank;
filling said tank with a fluid mixture comprising water, [and] ozone and an additive acting as a scavenger to thereby achieve an oxide growth on said substrate;
removing the oxide; and
drying the silicon wafer.